

ABSTRACT

An exposure apparatus is provided for performing exposure processes with high accuracy by accurately performing pressure control inside a chamber having a plurality of air-conditioning chambers. The inside of the main chamber which accommodates the exposure apparatus is divided into a plurality of air-conditioning chambers, and a pressure detection device which detects the pressure is provided with each of the plurality of air-conditioning chambers. Also, among the plurality of the air-conditioning chambers, the pressure inside a main column which accommodates an exposure stage on which a wafer is mounted and subjected to an exposure process, is set to be higher than the pressure of the other air-conditioning chambers based on detection results obtained from the pressure detection devices.